

## WHAT IS CLAIMED IS:

1. An electron beam projection mask for arranging a plurality of batch projection regions so that pattern density may be equalized all over a semiconductor substrate.

2. An electron beam projection mask according to claim 1,  
wherein the mask is a stencil type mask.

3. An electron beam projection mask according to claim 1,  
wherein the mask is a membrane type mask.

4. An electron beam projection mask according to claim 1,  
wherein the mask is a partial batch electron beam projection mask.

5. An electron beam projection mask according to claim 2,  
wherein the mask is a partial batch electron beam projection mask.

6. An electron beam projection mask according to claim 3,  
wherein the mask is a partial batch electron beam projection mask.

7. An electron beam projection mask as claimed in claim 1,  
wherein the mask is an electron beam projection

lithography mask.

8. An electron beam projection mask as claimed in claim 2,

wherein the mask is an electron beam projection lithography mask.

9. An electron beam projection mask as claimed in claim 3,

wherein the mask is an electron beam projection lithography mask.